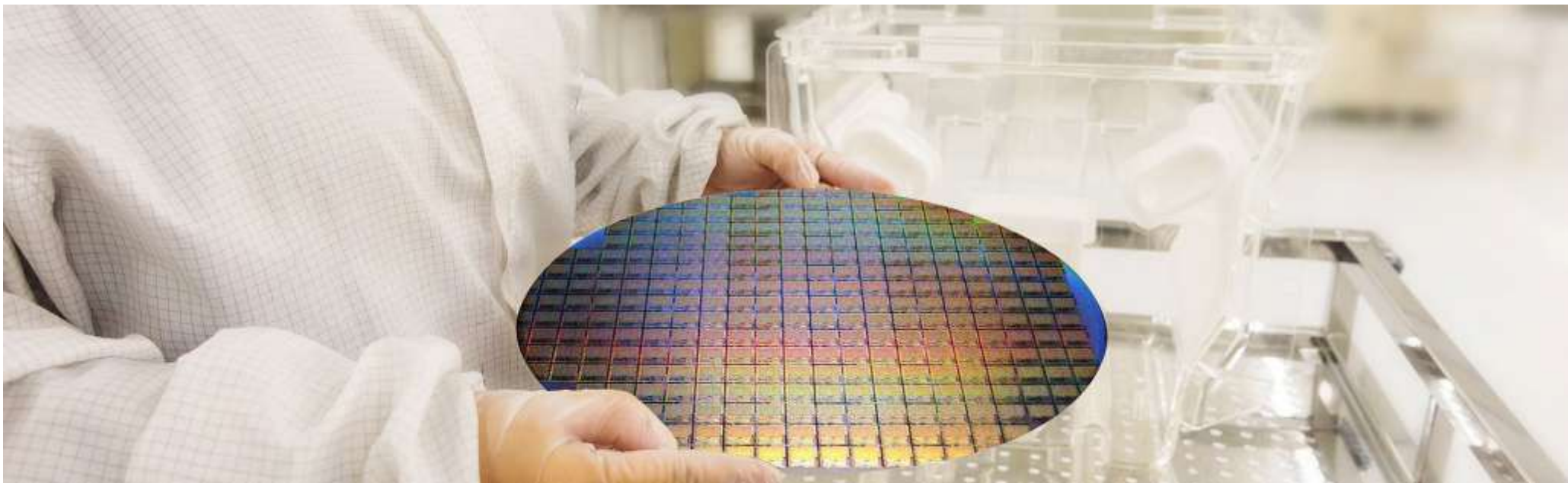




沉积温度对SCOT光电性能及表面形貌的影响



报告人：刘奕阳 2019.11.23

指导教师：孟凡英 刘正新



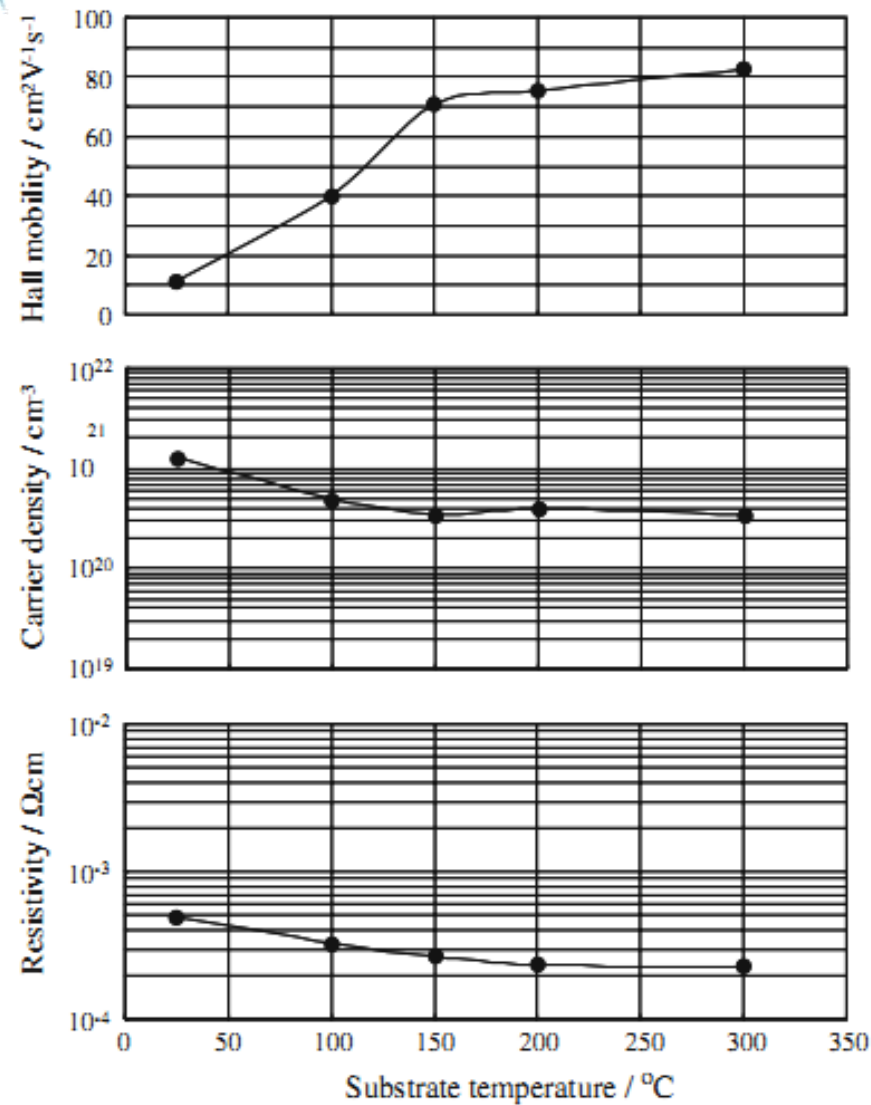
SCOT——材料及制备

SCOT成分wt%— In_2O_3 : ZrO_2 : TiO_2 : Ga_2O_3 = 98.5 : 0.5 : 0.5 : 0.5

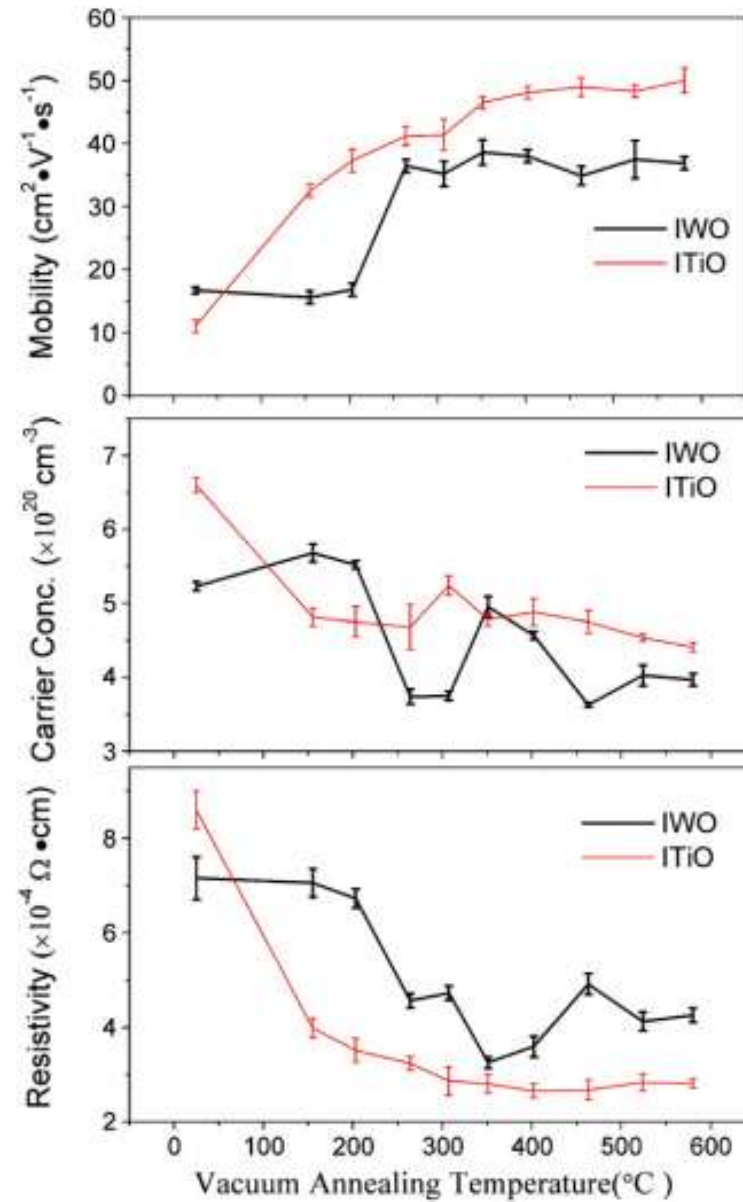
RF-sputter: $\text{Ar} + \text{O}_2$ 初始真空: $\sim 10^{-4} \text{Pa}$

功率	溅射压强	氧分压	薄膜厚度	沉积温度
120W	0.45Pa	0.008	70nm & 400nm	RT~160°C

Post annealing: air-200°C 30min



*Titanium-doped indium oxide films prepared by d.c. magnetron sputtering using ceramic target
Yoshiyuki Abe · Noriko Ishiyama*

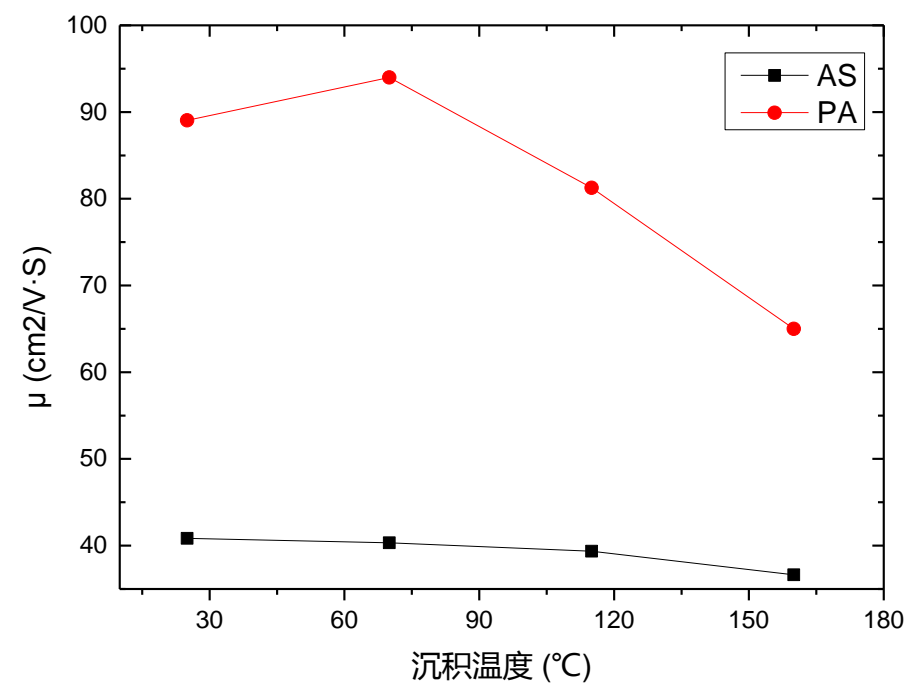
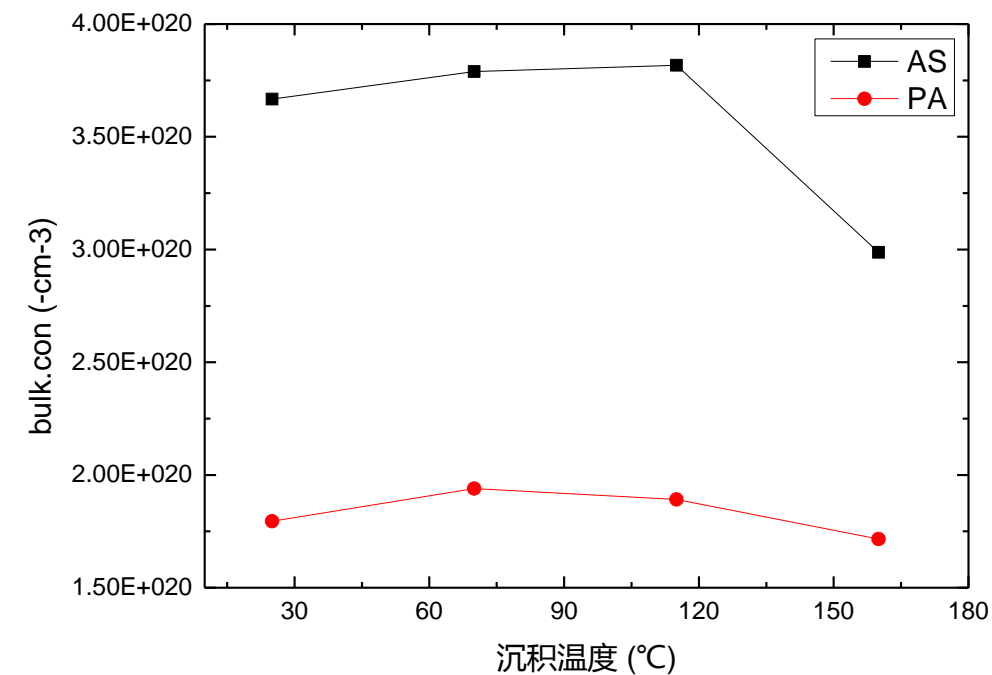
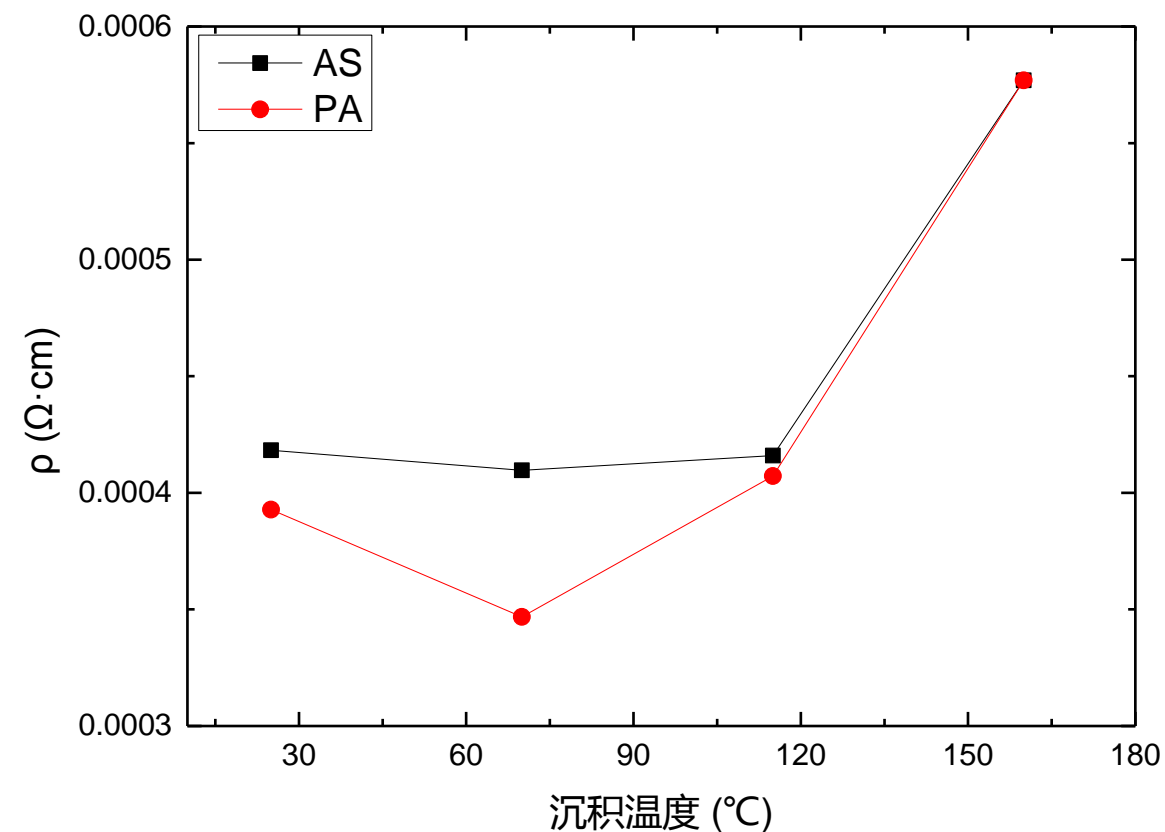


*Changes in the structural and electrical properties of vacuum post-annealed tungsten- and titanium-doped indium oxide films deposited by radio frequency magnetron sputtering
L.T. Yan , R.E.I. Schropp*

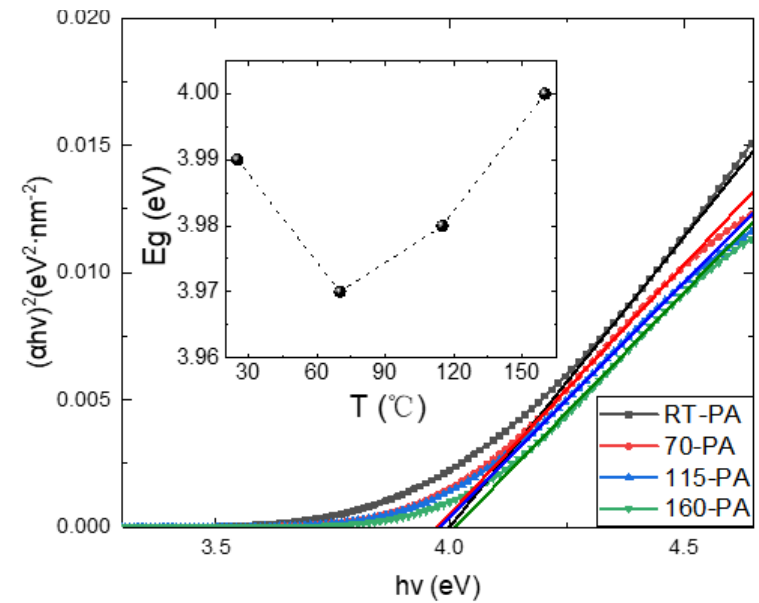
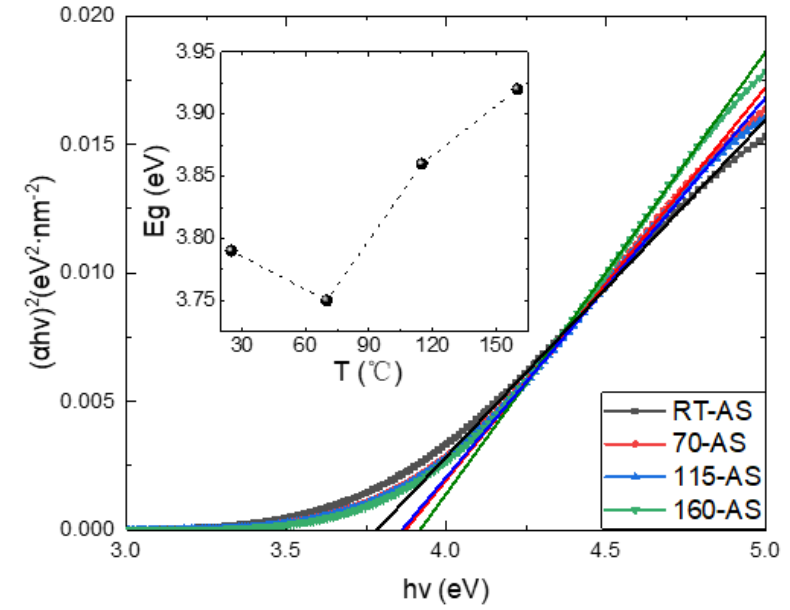
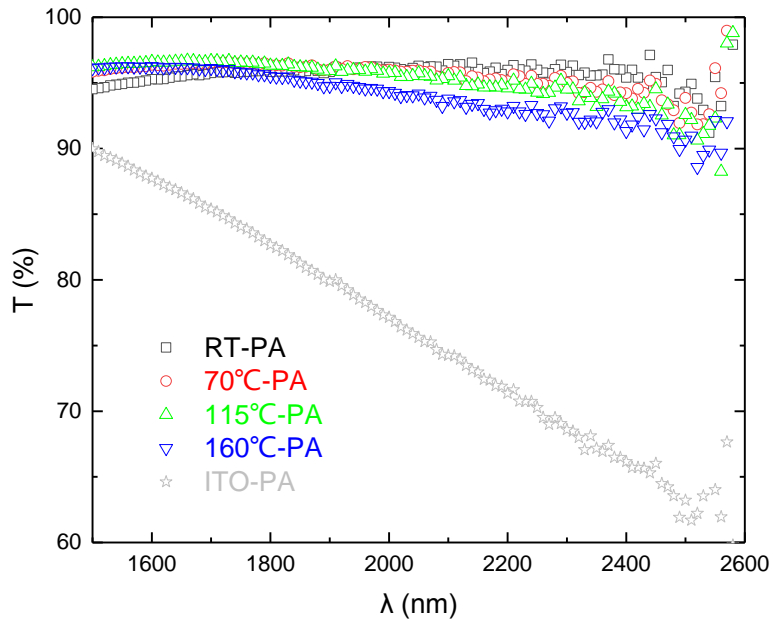
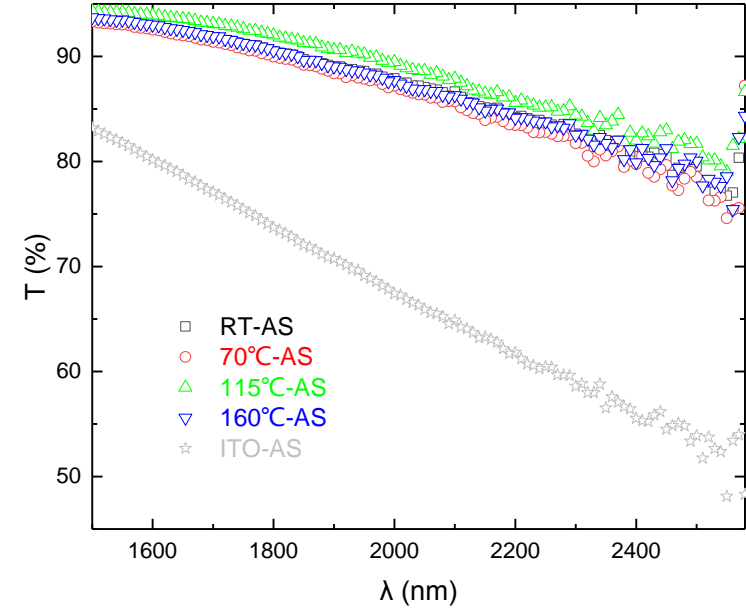
Fig. 4. Effect of post-annealing on the electrical properties of IWO and ITiO films deposited at 20 W for 1 h (error bars reflect the sample to sample variations).

Fig. 4 Substrate temperature dependency of resistivity, carrier density and Hall mobility of ITiO films of 1.6 at.% Ti-doping. Total gas pressure: 0.6 Pa, oxygen content in sputtering gas: 1 vol.%. Film thickness: 500 nm

SCOT温度系列-电学性能

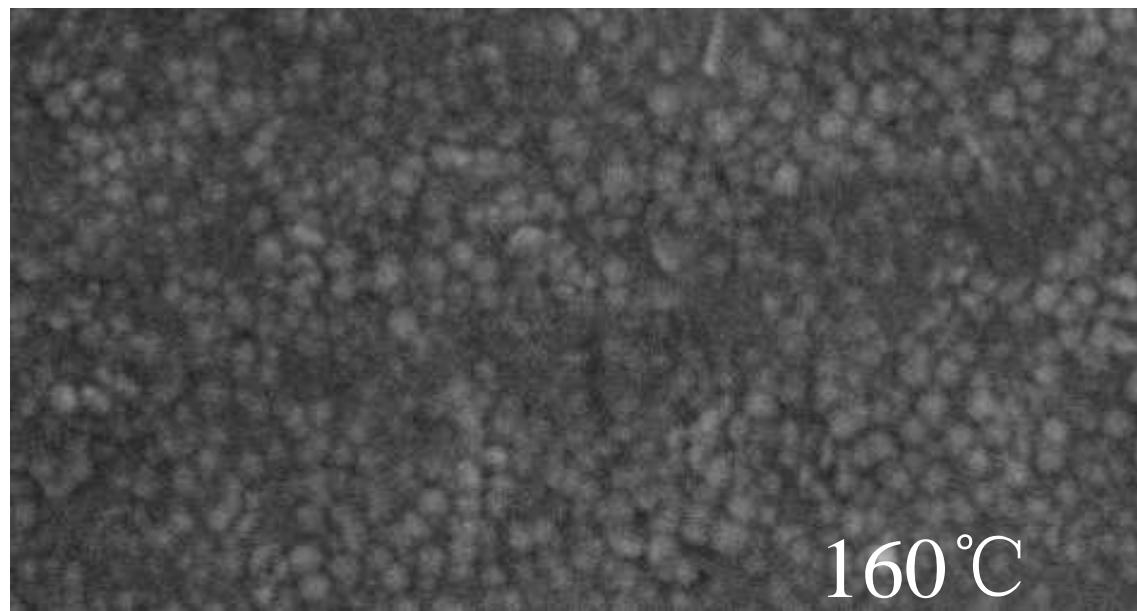
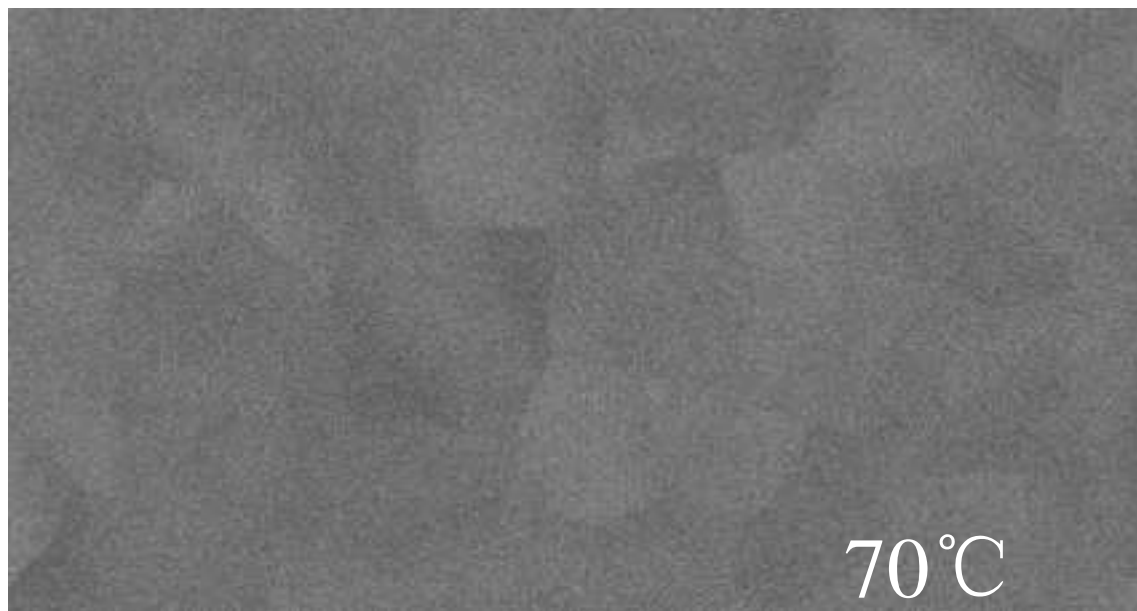
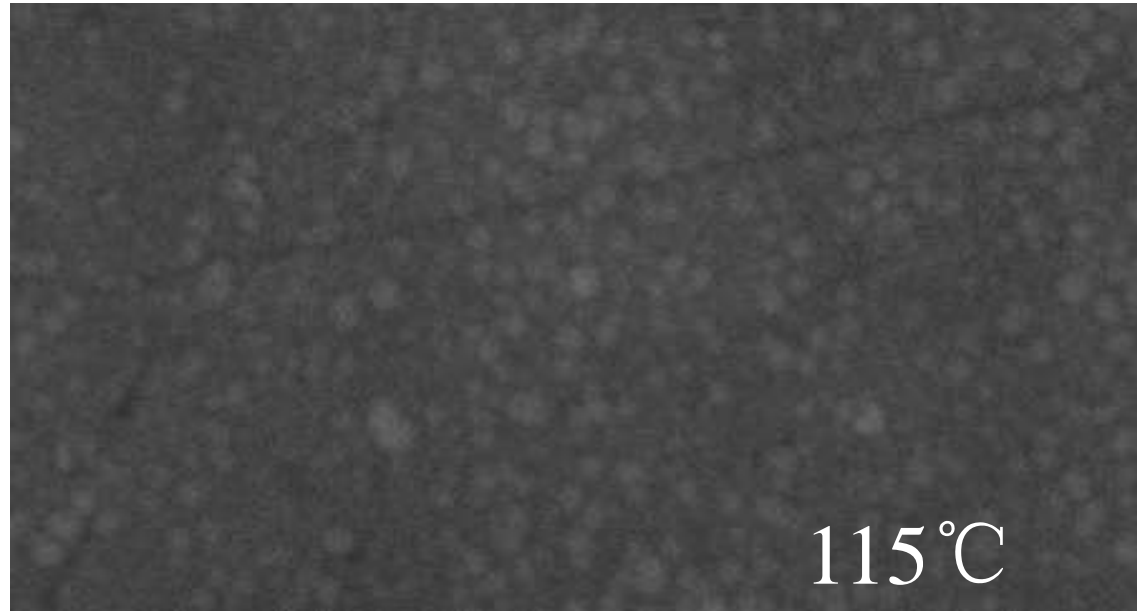
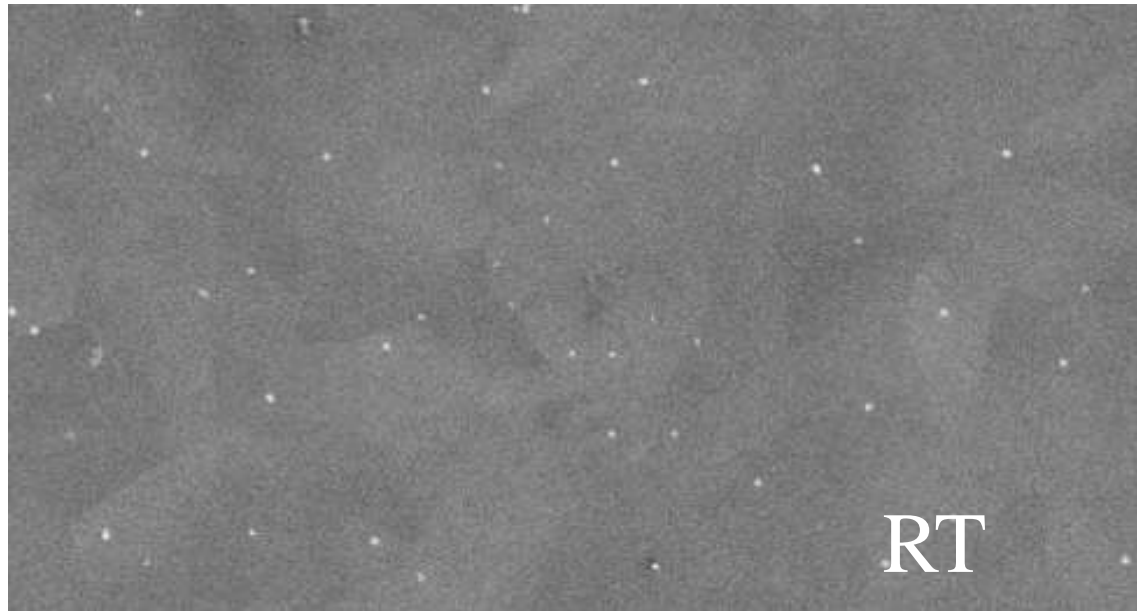


SCOT温度系列-光学性能

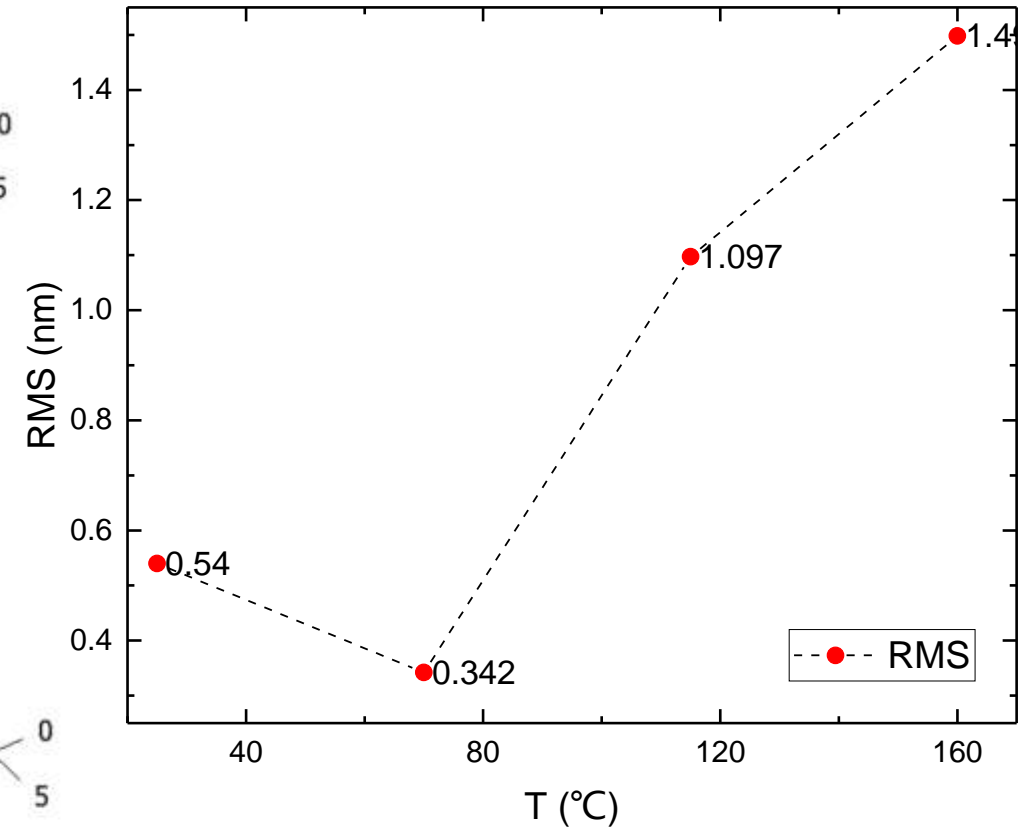
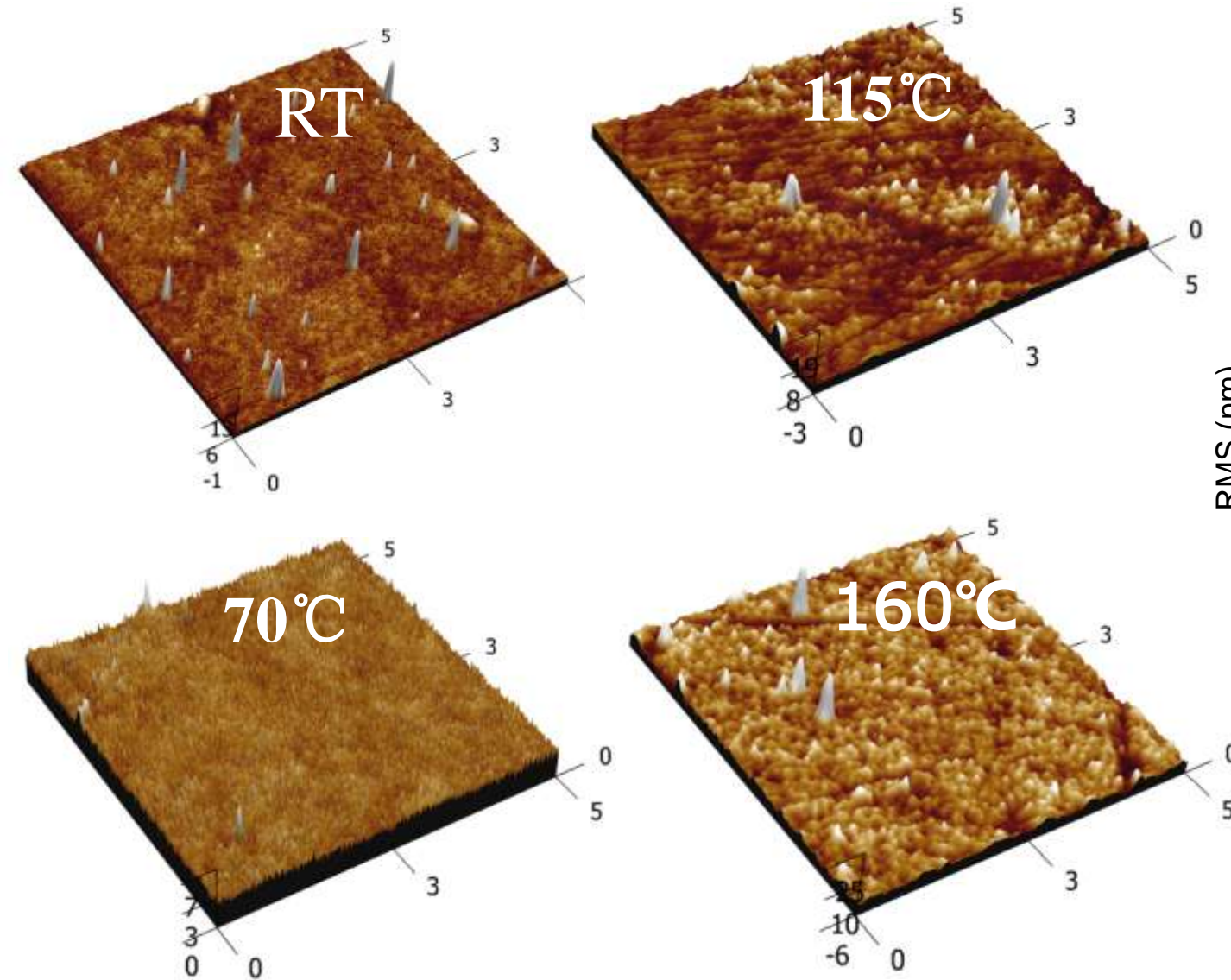


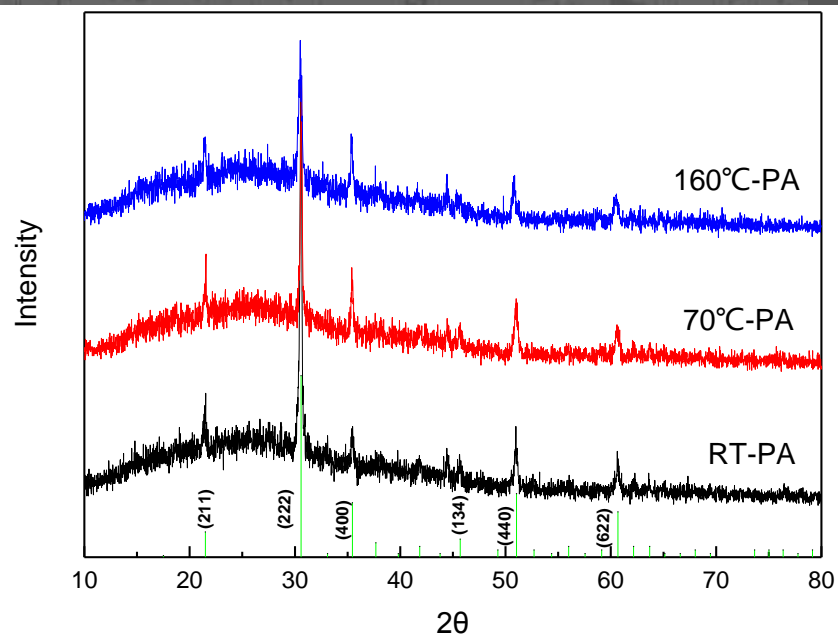
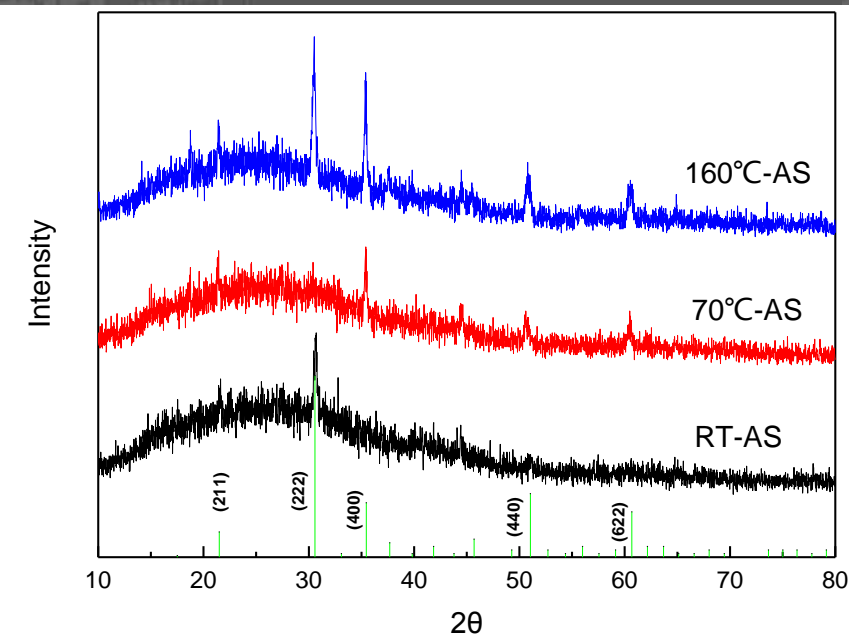
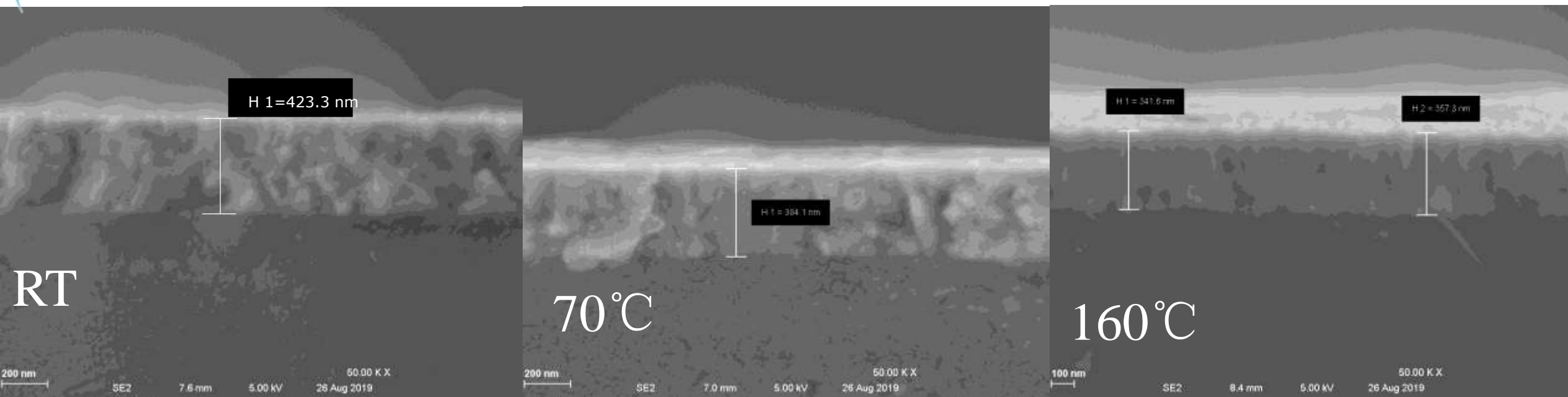


SCOT-SEM-PA-70nm



SCOT-AFM-PA

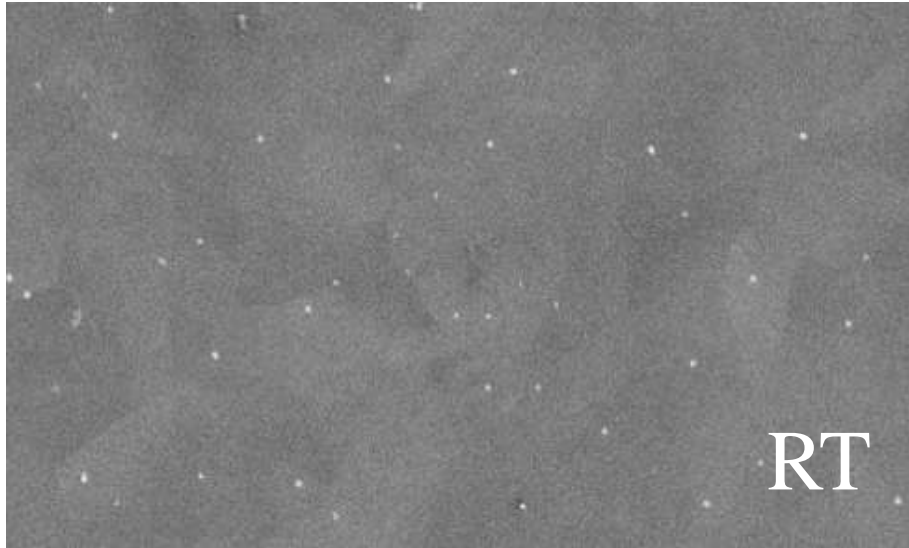




所有薄膜表现出与标准IO一致的晶向；不同沉积温度下，薄膜表现出不同的择优取向，而退火之后择优取向被消除。

关于室温沉积下SCOT薄膜表面白色颗粒的分析

颗粒尺寸太小，直接表征困难，EDS结果不理想，XPS、SIMS无法探测

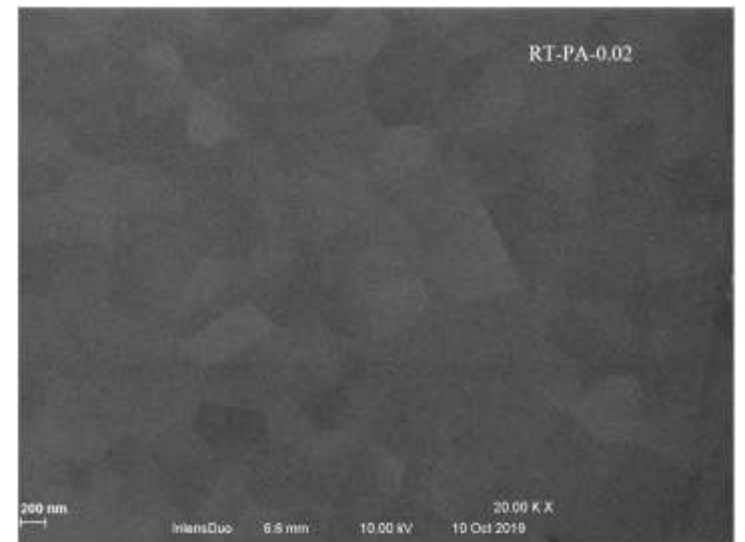
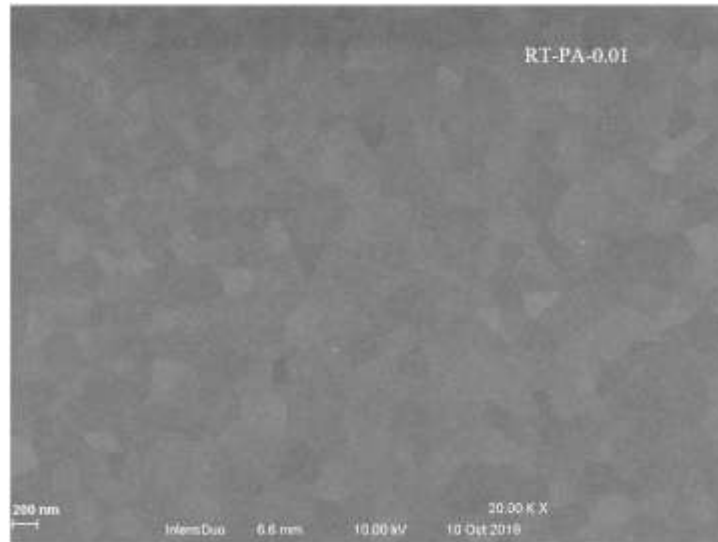


元素种类	熔点	沸点
In	156.61℃	2060℃
Zr	1852 ± 2℃	4377℃
Ti	1668℃	3287℃
Ga	29.8℃	2403℃

$RT < 29.8^{\circ}\text{C} < 70^{\circ}\text{C} < 115^{\circ}\text{C} < 160^{\circ}\text{C}$

四种元素的金属活动性顺序：Ti > Zr
> Ga > In

熔化→析出→蒸发



总结

- 1、SCOT电学性能随温度升高先增强再降低，而且具有不同于传统TCO材料的低温特性；
- 2、相对于主流的ITO，SCOT在长波段的透过性表现优秀；
- 3、温度对SCOT薄膜表面的粗糙程度影响很大；
- 4、结晶质量越好，光学带隙越小；
- 5、氧不足和低温同时存在的情况下，会影响SCOT中Ga元素的有效掺杂；
- 6、高温沉积使薄膜更致密。



Thank you !
